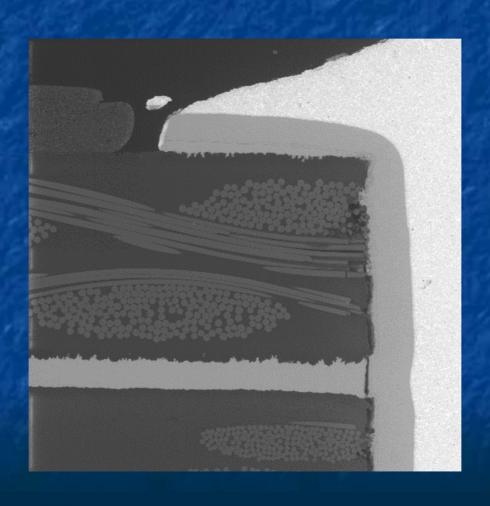
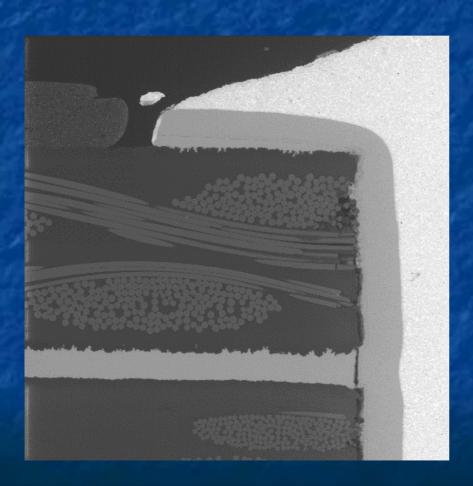
Images of Failures in Microelectronics Packaging and Assembly

Ed Hare, Ph.D./SEM Lab, Inc.

IMAPS NW - Feb. 11th 2004 Redmond, WA

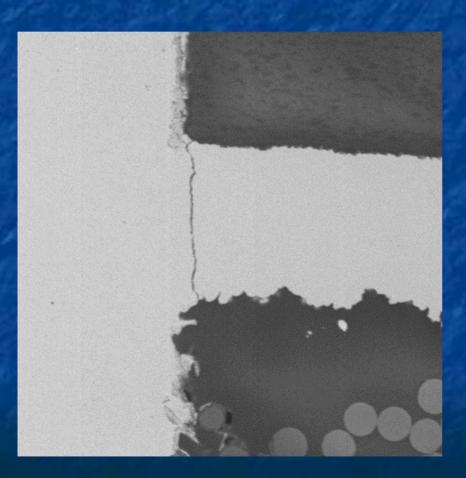


Inner Layer Separation

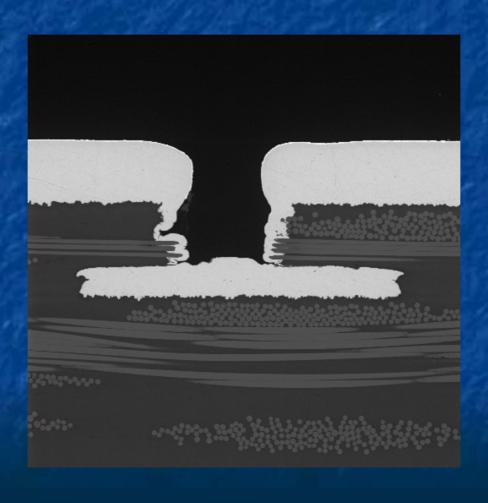


- Between laminate copper and electroless copper
- Found Ca & S residues at failed interface

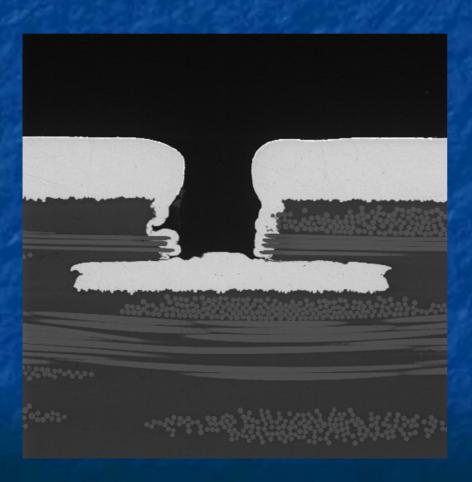
Inner Layer Separation



- QC coupon mount from PWB fabricator
- "lines of demarcation"
- Missed during routineQC examination

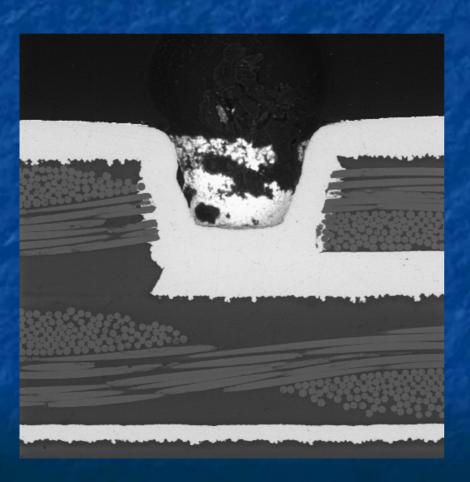


Microvia

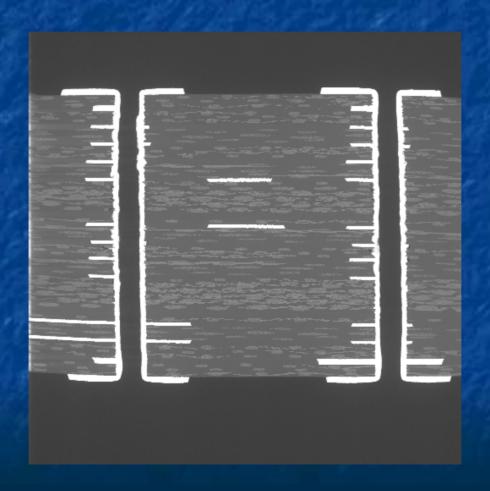


- This is a poorly fabricated microvia
- There is little or no copper plating connecting to the layer-2 pad

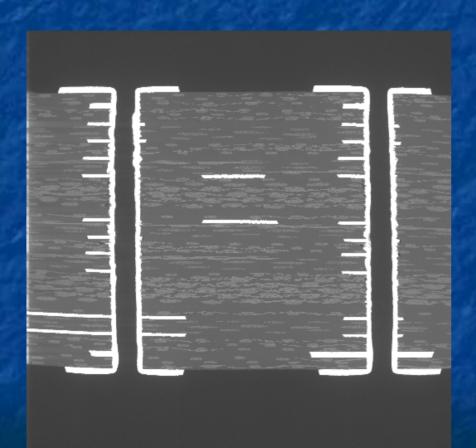
Microvia



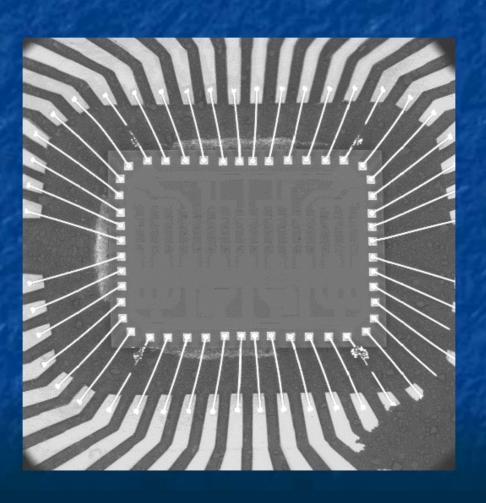
- This is a "good" microvia
- There is uniform copper plating connecting to the layer-2 pad

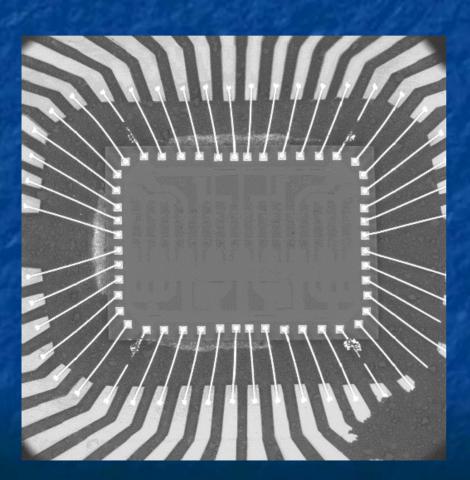


Drill Breakout



- The inner layer lands probably should have been larger diameter in this design
- This condition fails
 Class 3 criteria in IPC-A-600 (min. annular ring 0.001 in)

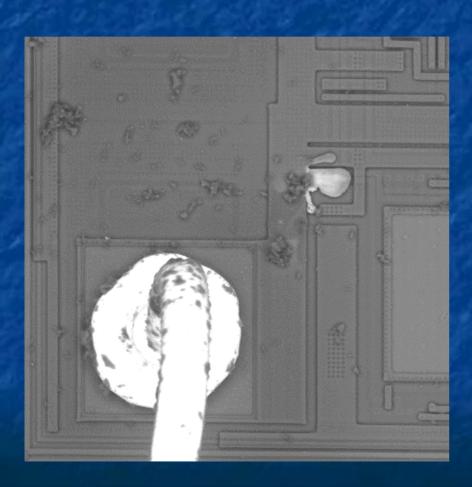




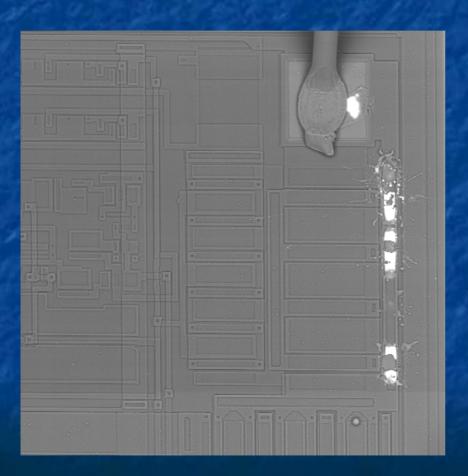
- All four Vcc wire bonds are fused open
- There is no damage on the die
- Excessive current failure likely due to latch-up



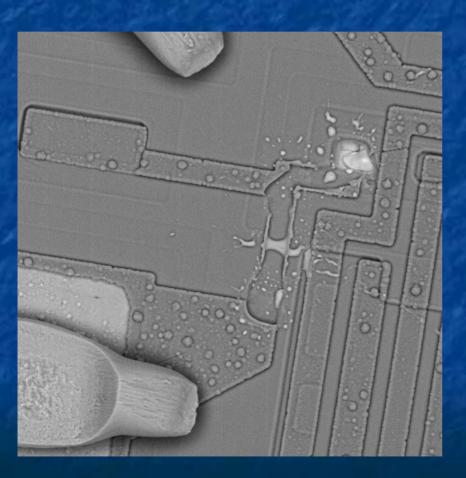
- Vcc wire bond is fused open
- Fusing current of 1mil gold wire is ~ 0.75 amps



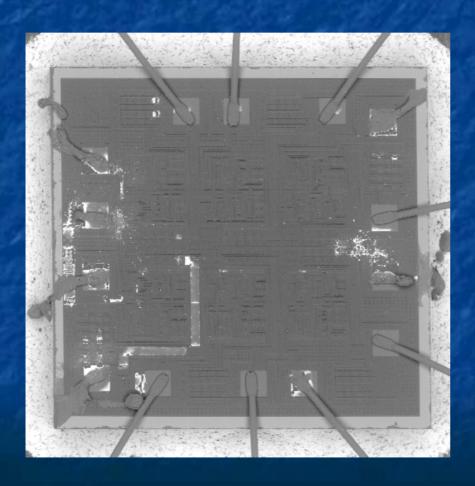
- A short segment of metallization was fused open
- Likely caused by a voltage transient



- A short segment of metallization was fused open
- Likely caused by a voltage transient



- A short segment of metallization was fused open
- Likely caused by a voltage transient or ESD

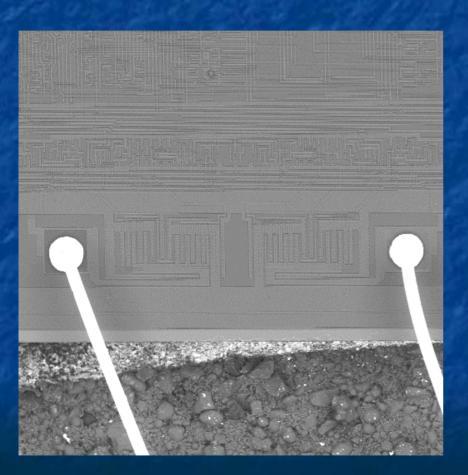


Gross electrical overstress damage

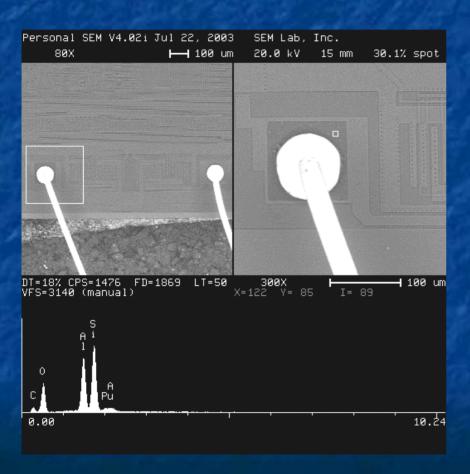




- Contributing causes
 - * moisture
 - * "pop-corn" damage
 - * internal delam
 - * P contamination



- How to avoid –* MSD control
- Use CSAM imaging and F/A to diagnose



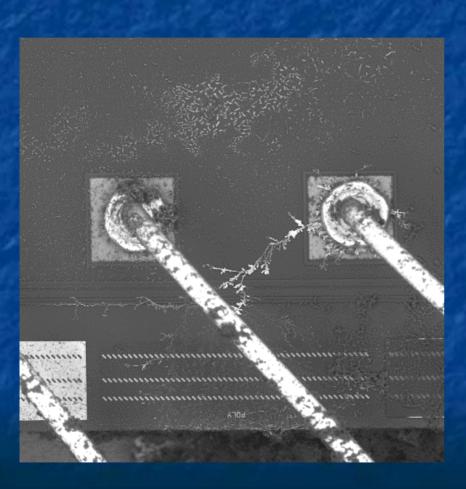
- Trace of P
- P due to molding compound or residual from IC fab



Bright spots are Ti-W barrier layer where Al is missing

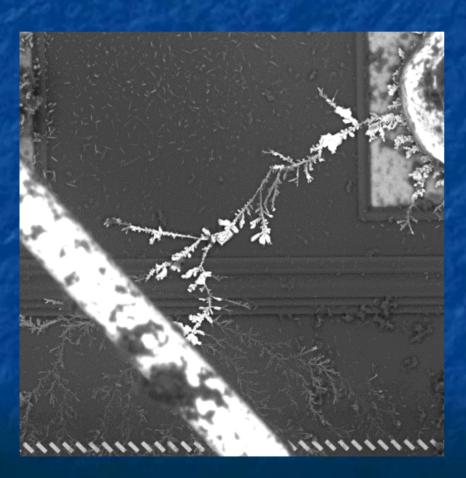


Dendritic Growth on IC Die

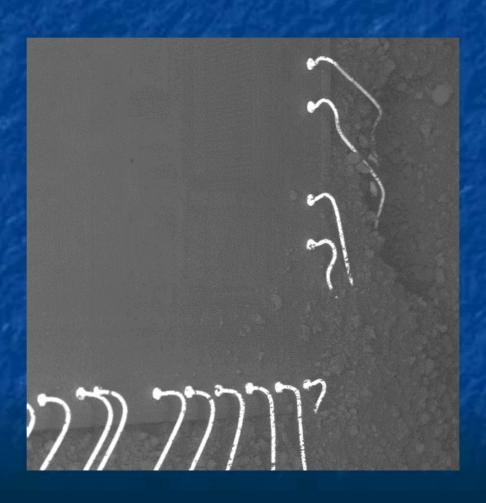


- Silver and copper dendrites
- For all the same reasons as bond pad corrosion

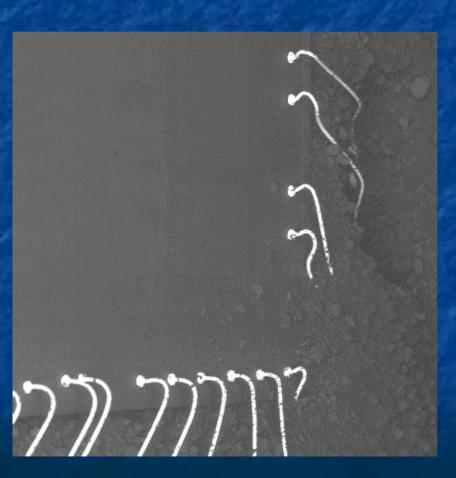
Dendritic Growth on IC Die



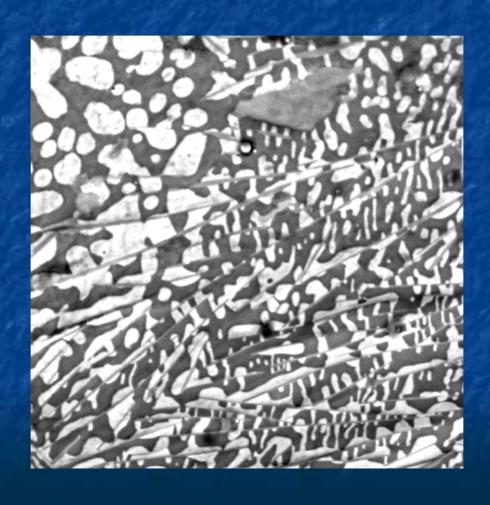
- ... or most of the same reasons as bond pad corrosion
 - moisture
 - ionic contamination
 - bias
 - internal delam



Bond Wire Sweep



Bond wires are sweptby the injectionmolding compound



Gold Embrittlement



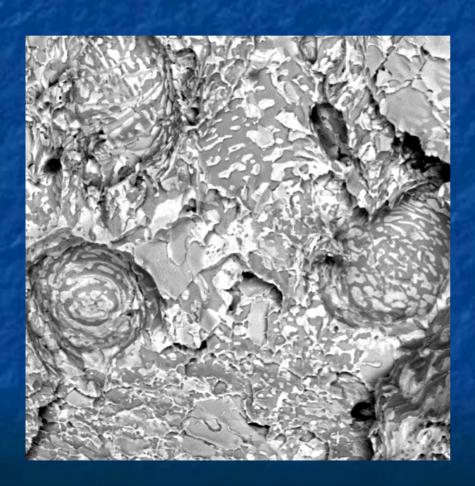
- This is gold-embrittled eutectic Sn-Pb solder
- AuSn4 & AuSn2
 platelets dispersed
 throughout the
 microstructure

Gold Embrittlement

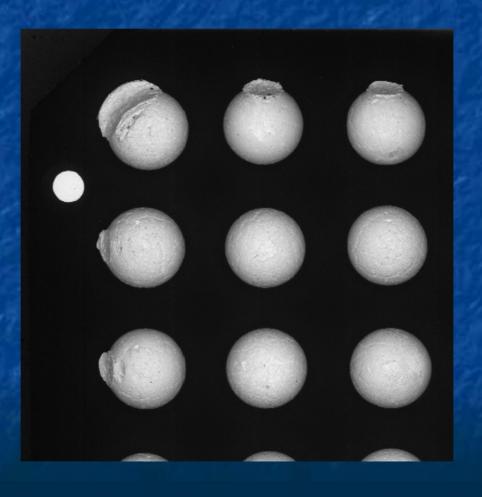


- Theory the goldembrittlement caused voiding!
- AuSn4 & AuSn2platelets trap volatiles

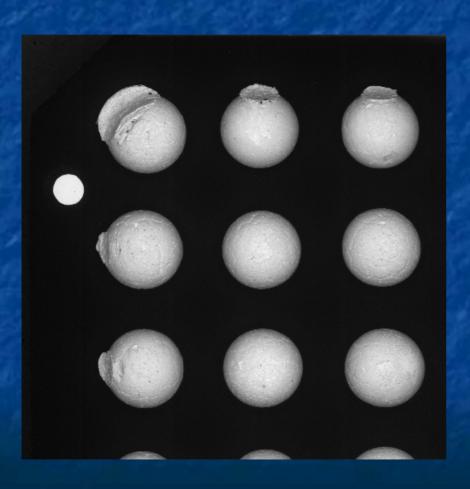
Gold Embrittlement



- Theory the goldembrittlement caused voiding!
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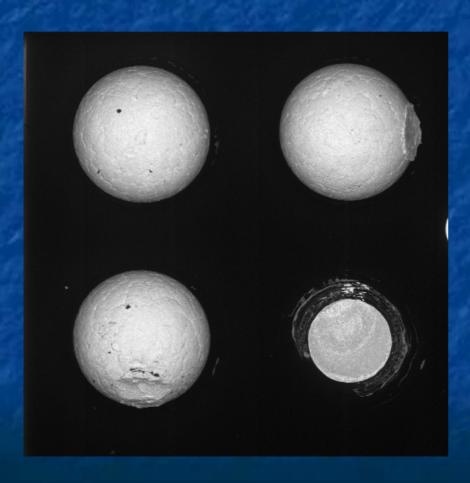


BGA Mechanical Damage

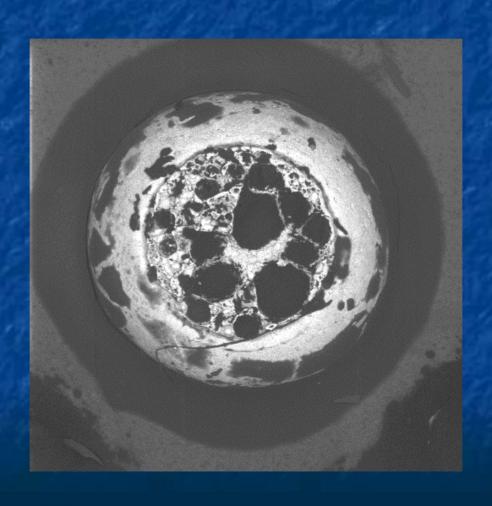


- Probably tool damage
- Most extreme cases had missing balls

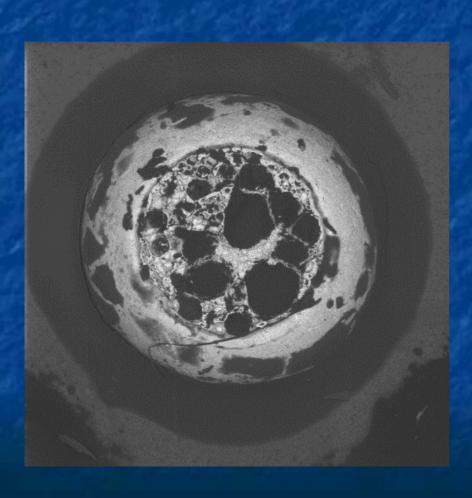
BGA Mechanical Damage



Corner has a missing ball

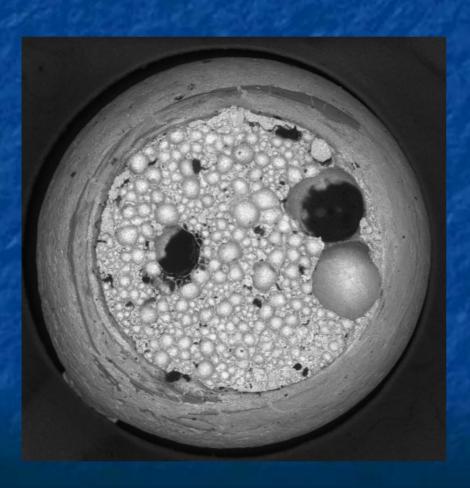


BGA Solder Joint Failure



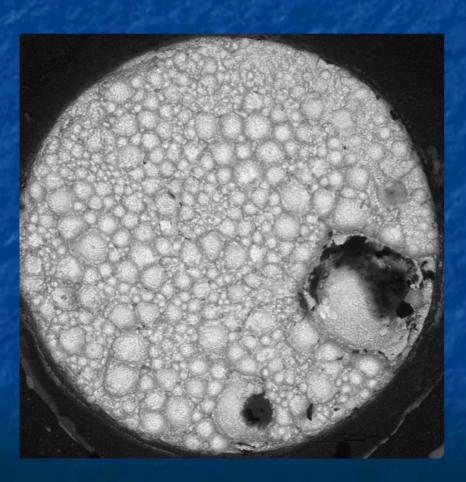
- BGA solder joint failed at the BGA substrate
- Entrapped material includes flux and mask constituents
- Probably flux and mask are chemically incompatible

BGA Solder Joint Failure



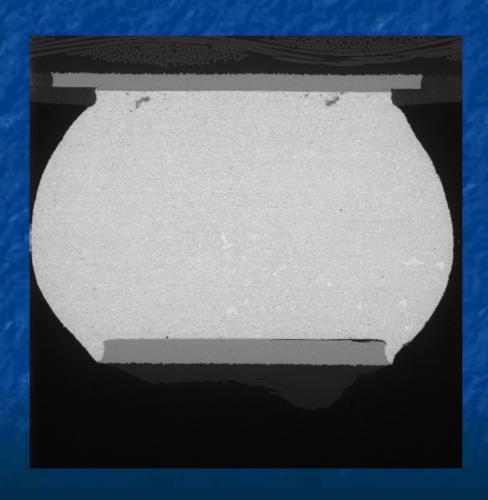
- This is a different example
- Entrapped material likely debris from plastic trays

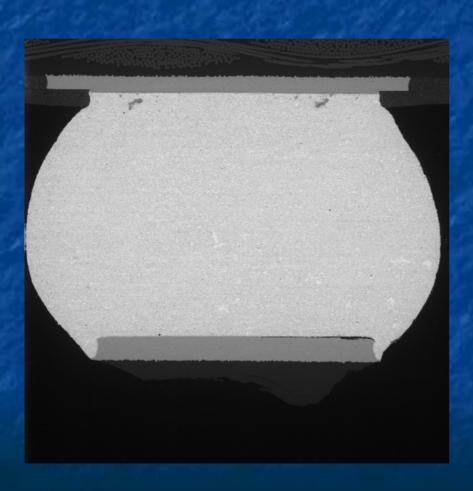
BGA Solder Joint Failure



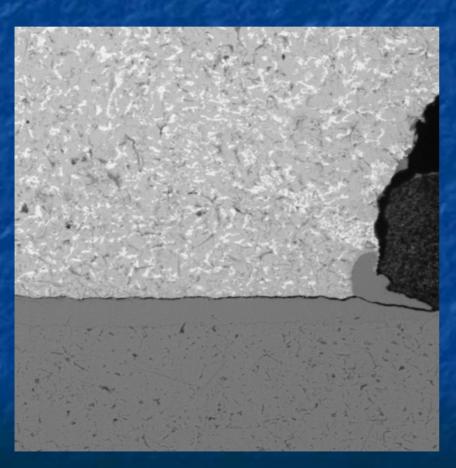
- This is the fracture surface at the BGA substrate (different location)
- IPC specifications allow up to 25%

What is this?

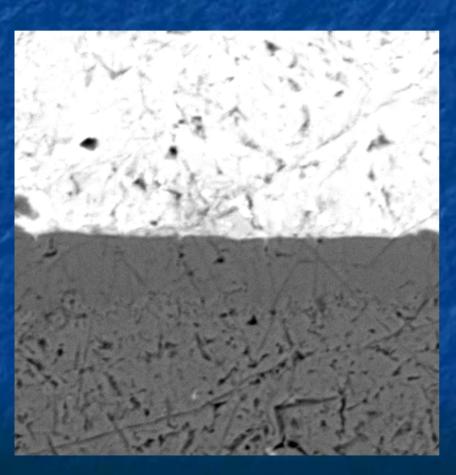




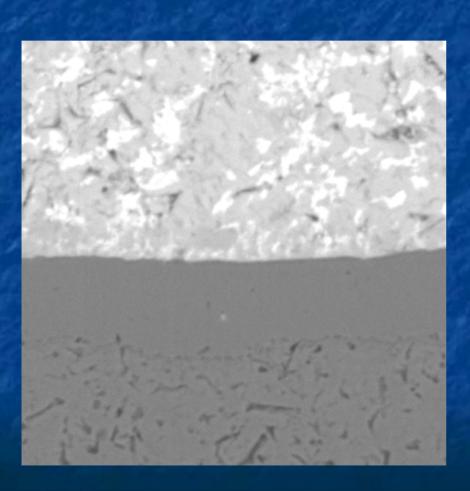
- Brittle fracture at the solder/PWB pad interface
- More specifically between the Ni3Sn4 IMC layer and the Prich EN



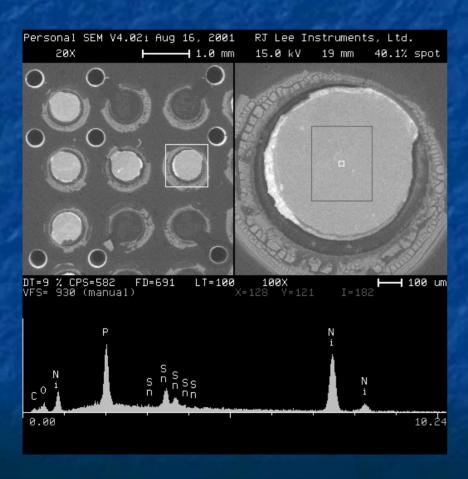
Very fine line brittle fracture at the solder/PWB pad interface



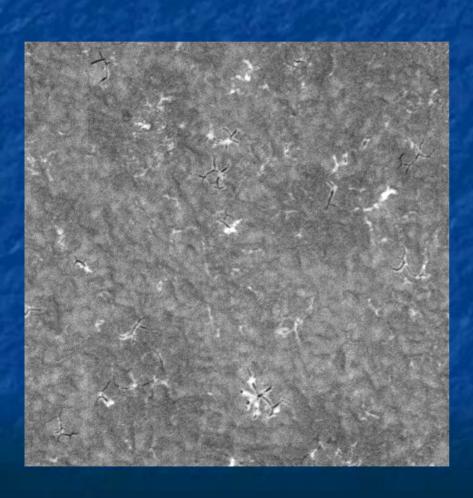
Very thin (~ 0.25 micron) P-rich EN layer in contact with the Ni3Sn4 IMC layer



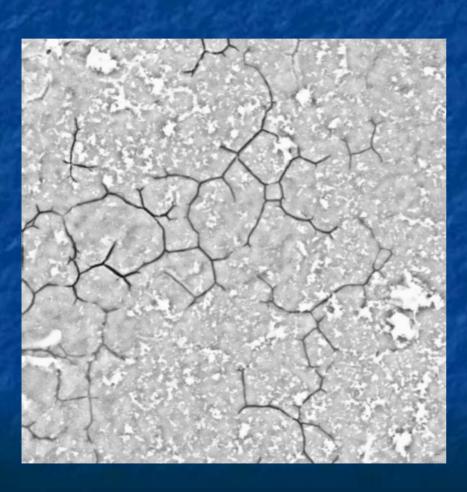
- 2nd example
- Very thin (~ 0.25 micron) P-rich EN layer in contact with the Ni3Sn4 IMC layer



~ 18 wt% P at the fracture surface versus 7 – 9 wt% P for EN bulk

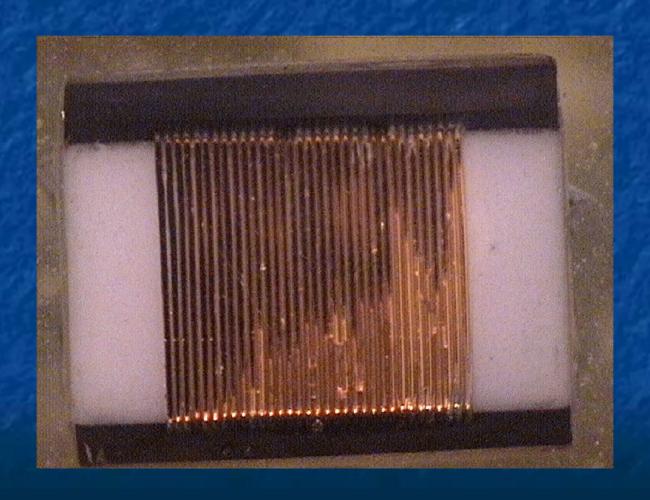


- IG spiking
- Hyper-etching of EN in IG bath



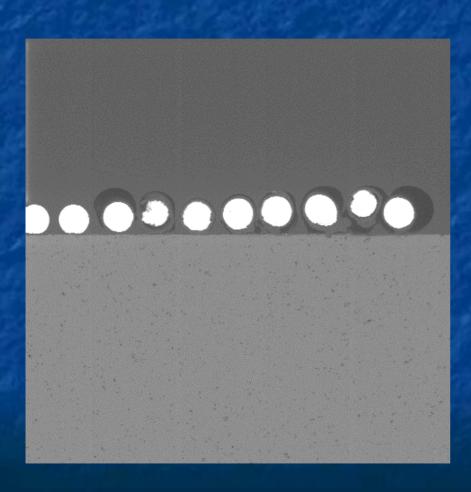
- 2nd example
- IG spiking
- Hyper-etching of EN in IG bath

What is this?

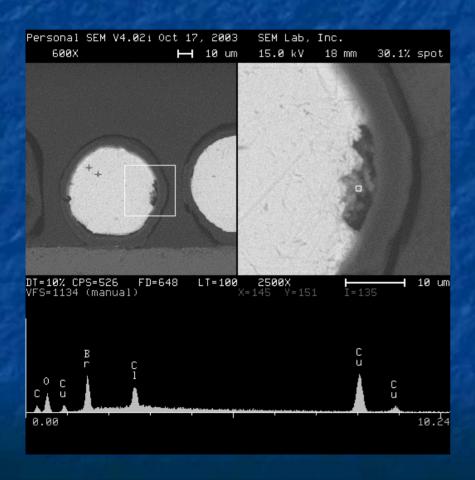




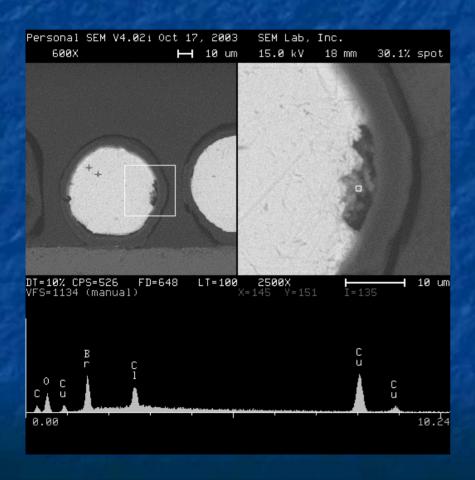
- Discoloration of magnet wire
- Open circuited coil



- Encapsulant voids around magnet wire
- Magnet wire crosssection reduced due to corrosion

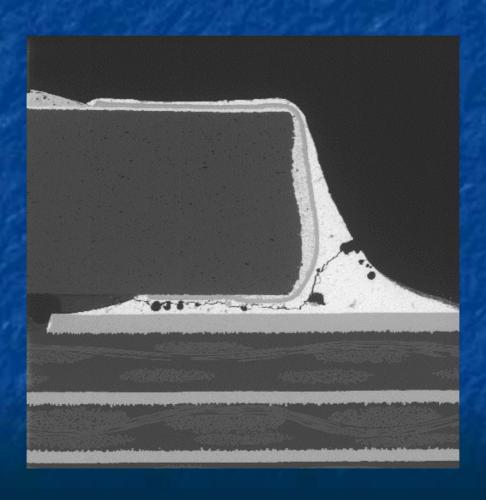


 Corrosion due to Cl & Br from activated flux that wicked into the coil

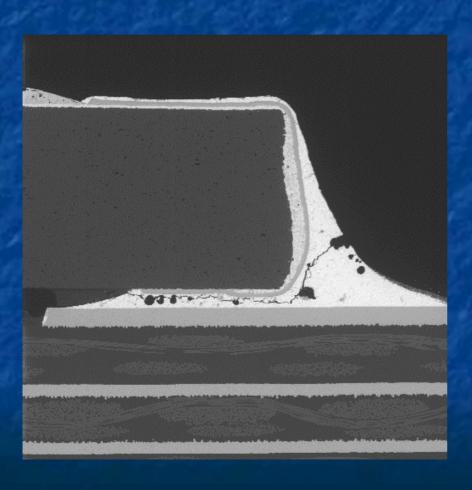


 Corrosion due to Cl & Br from activated flux that wicked into the coil

What is this?

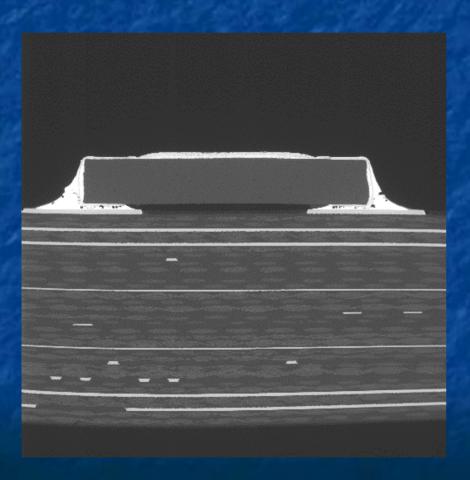


Failed Resistor Network Joint



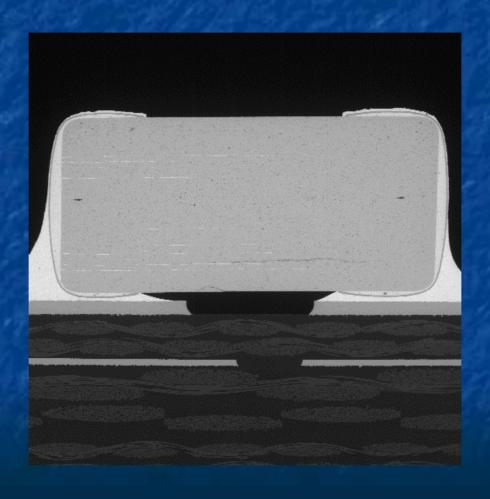
- Classic thermal fatigue failure
- Voids may be a contributing factor

Failed Resistor Network Joints

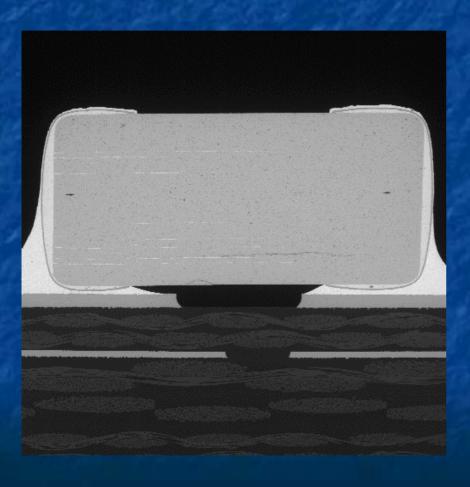


- Classic thermal fatigue failure
- Thermal expansion mismatch too large
- Failed after ~ 5 years of service

What is this?

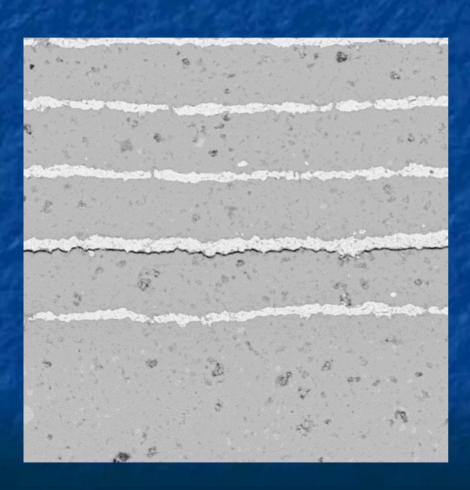


MLCC Knit Line Failure



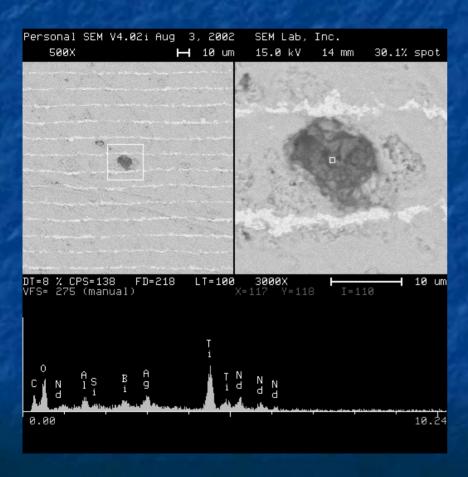
- MLCC manufacturing defect
- Crack propagates and crosses plates causing electromigration short

MLCC Knit Line Failure



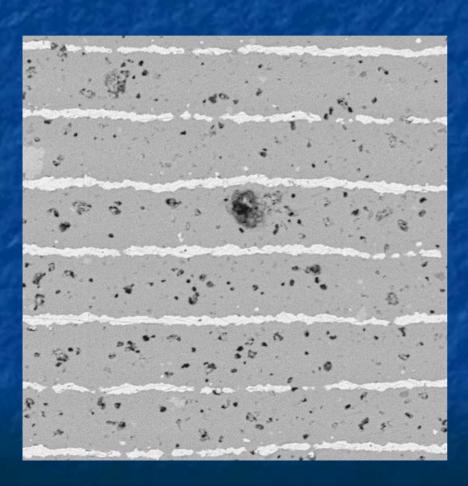
Delamination between plate and dielectric

MLCC Dielectric Voids



Void bridges plates and creates electromigration path

MLCC Dielectric Voids



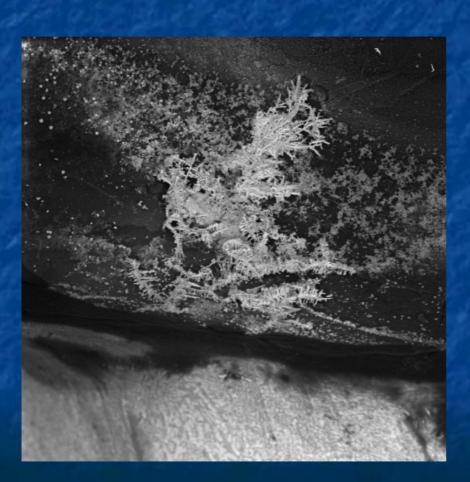
Another example of MLCC dielectric voids

What is this?

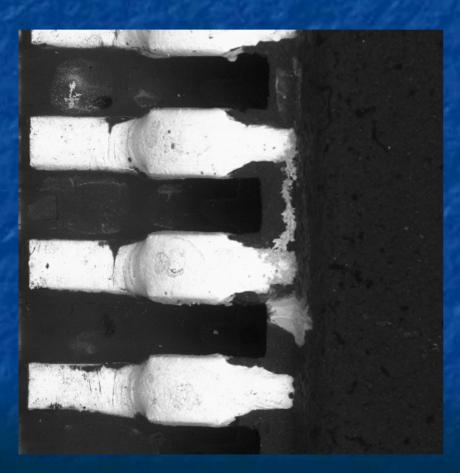




- Electrical leakage failures
- No Clean Flux, but likely activated flux used in touch up



- Pb dendrites grow between signals and short them out
- Never mix No-Clean flux and activated flux



Its even growing across the mold flash up by the package body!



There is nothing quite like a pretty picture of a Pb-dendrite

CONCLUSIONS

- Dendrites? Go ahead, make my day ...
- Bond pad corrosion? Bring it on!
- Black pad syndrome? Not a HASL

■ Ed Hare, Ph.D./<u>SEM Lab, Inc.</u>